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Total number of printed pages - 3

B. Tech

PCEC 4401

Seventh Semester Back Examination – 2014 VLSI DESIGN

BRANCH (S): AEIE, EC, ETC, IEE

QUESTION CODE: L 146

Full Marks - 70

NTRAL

Time: 3 Hours

Answer Question No. 1 which is compulsory and any five from the rest.

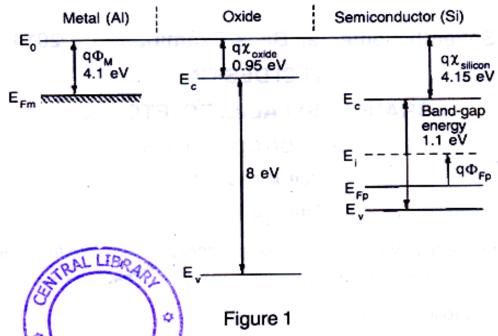
The figures in the right-hand margin indicate marks.

Answer the following questions :

2 × 10

- (a) What is channel-stop implantation?
- (b) How Power density varies with constant voltage scaling?
- (c) Draw the schematic diagram of an XOR gate using CMOS Transmission gates.
- (d) Realize AND and NAND logic using CPL.
- (e) Draw the stick diagram of a 2-input NOR gate using CMOS technology.
- (f) What are the stages where a VLSI chip can be tested?
- (g) What is Dynamic CMOS Logic?
- (h) What is pseudo logic circuit?
- (i) What is domino logic?
- (j) Why does CMOS dissipate power when its input changes from 1 to 0 or from 0 to 1?
- (a) With the help of Band diagram, describe the operation of NMOSFET.
 - (b) Consider the MOS structure that consists of a p-type doped silicon substrate, a silicon dioxide layer, and a metal (aluminum) gate. The equilibrium Fermi potential of the doped silicon substrate is given as $q_{\Phi_{Fp}} = 0.2 \text{ eV}$. Using the electron affinity for silicon and the work function for aluminum

given in Figure 1 below, calculate the built-in potential difference across the MOS system. Assume that the MOS system contains no other charges in the oxide or on the silicon-oxide interface.



3. Consider the CMOS inverter circuit shown in Figure 2 below, with V_{DD} = 3.3 V. The I-V characteristics of the nMOS transistor are specified as follows: when V_{GS} = 3.3 V, the drain current reaches its saturation level I_{Dsat} = 2 mA for V_{DS} = 2.5 V. Assume that the input signal applied to the gate is a step pulse that switches instantaneously from 0 V to 3.3 V. Using the data above, calculate the delay time necessary for the output to fall from its initial value of 3.3 V to 1.65 V, assuming an output load capacitance of 300 fF.

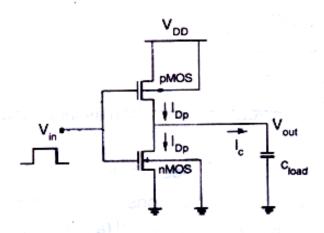


Figure 2

4. A company has access to a CMOS fabrication process with the device parameters listed below:

 $\mu_{\rm n} \rm C_{\rm ox}$ = 120 μ A/V², $\mu_{\rm p} \rm C_{\rm ox}$ = 60 μ A/V², $\rm V_{TO,n}$ = 0.8 V, $\rm V_{TO,\rho}$ = -1.0 V, L = 0.6 μ m for both nMOS and pMOS devices and $\rm W_{\rm min}$ = 1.2 μ m.

Design a CMOS inverter by determining the channel widths W_n , and W_p of the nMOS and pMOS transistors, to meet the following performance specifications.

- V_{th} = 1.5 V for VDD = 3 V,
- * Propagation delay times $\tau^*_{PHL} \le 0.2 \text{ ns and } \tau^*_{PLH} \le 0.15 \text{ ns,}$
- A falling delay of 0.35 ns for an output transition from 2 V to 0.5 V, assuming a combined output load capacitance of 300 fF and ideal step input.
- (a) For the Boolean expression Y = (A + B + C)·(D + E) using CMOS, find the equivalent CMOS inverter circuit for simultaneous switching of all inputs, assuming that (W/L)_P = 15 for all PMOS transistors and (W/L)_N = 10 for all NMOS transistors.
 - (b) Implement a Full Adder circuit using CMOS.
- (a) Explain how the Transmission Gate transfers both logic '0' and logic '1' efficiently.
 - (b) Implement a 4:1 Multiplexer using Transmission Gates. 45
- (a) Discuss about FPGA based VLSI design.
 - (b) Describe the operation of four transistor resistive load SRAM cell. 5
- 8. Write short note on any two of the following:
 - (a) Constant-Voltage Scaling
 - (b) Constant-Field Scaling
 - (c) DIBL
 - (d) HCI.

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5×2